REMARKS

Claims 1-90 are pending. By this Amendment, claims 47-90 are added, and claims 16, 19, 22, 33 and 34 are amended. The attached Appendix includes marked-up copies of each rewritten claim (37 C.F.R. §1.121(c)(1)(ii)).

The November 19, 2002 RCE requested that prosecution be suspended. Upon entry of this Amendment and the Information Disclosure Statement filed herewith, Applicant requests that prosecution be resumed. Applicant requests the Examiner to consider the references submitted in the attached Information Disclosure Statement, along with the references submitted with the Information Disclosure Statement that was filed with the RCE on November 19, 2002.

Examination and allowance in due course are earnestly solicited.

Respectfully submitted,

Mario A. Costantino
Registration No. 33,565

MAC/nra

Attachments:
Appendix
Amendment Transmittal
Information Disclosure Statement

Date: December 16, 2002

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

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APPENDIX

Changes to Claims:

Claims 47-90 are added.

The following is a marked-up version of the amended claims:

16. (Amended) The exposure apparatus of claim 1, wherein the illumination optical system comprises:

a ~~light~~ radiation source that outputs ~~the light~~a radiation beam;

a reflective optical integrator that makes uniform an illumination distribution of ~~light~~ radiation from the ~~light~~ radiation beam; and

a ~~light~~ radiation guiding optical system arranged in an optical path between the ~~light~~ radiation source and the reflective optical integrator, and that guides the ~~light~~ radiation beam from the ~~light~~ radiation source to the reflective optical integrator.

19. (Amended) An exposure apparatus comprising:

an illumination optical system having a plurality of reflective components that guide a ~~light~~ radiation beam to a mask;

a projection system that projects a pattern of the mask onto a photosensitive substrate;

a drive that relatively moves the photosensitive substrate and the mask with respect to the projection system along a specified scanning exposure direction;

a first telecentricity adjustment mechanism that applies an oblique component to telecentricity in one of: (a) an exposure field of the projection system, and (b) an illumination field formed on the mask; and

a second telecentricity adjustment mechanism that adjusts telecentricity changing in accordance with a position from an optical axis in one of: (a) the exposure field of the projection system, and (b) the illumination field formed on the mask;

wherein the first and second telecentricity adjustment mechanisms respectively adjust at least some of the plurality of reflective components of the illumination optical system.

22. (Amended) The exposure apparatus of claim 19, wherein the illumination optical system comprises:

a ~~light~~ radiation source that outputs the ~~light~~ radiation beam;

a reflective integrator that makes uniform an illumination distribution of ~~light~~ radiation from the ~~light~~ radiation beam on the photosensitive substrate or the mask; and

a ~~light~~ radiation guiding optical system arranged between the ~~light~~ radiation source and the reflective integrator that guides the ~~light~~radiation beam from the ~~light~~radiation source to the reflective integrator.

33. (Amended) The method of claim 32, wherein the oblique component to telecentricity is applied by adjusting an illumination optical component that is different from the ~~at least one common~~different illumination optical ~~component~~components, and the telecentricity changing in accordance with a position from the optical axis is adjusted by adjusting an illumination optical component that is different from the illumination optical component adjusted to apply the oblique component to telecentricity.

34. (Amended) The method of claim 32, wherein the oblique component to telecentricity is applied by adjusting an illumination optical component that is different from the ~~at least one common~~different illumination optical ~~component~~components, and the telecentricity changing in accordance with a position from the optical axis is adjusted by adjusting an illumination optical component that is the same as the illumination optical component adjusted to apply the oblique component to telecentricity.